

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L2	0	((semiconductor with insulat\$4) or SOI) and (hard with mask) and ((opening or trench or via or recess) with semiconductor) and (lateral with (etching or removing)) and implant\$5 and (anneal\$3 or heat\$3) and ((fill\$3 or deposit\$3) with (opening or trench or via or recess)) and (remov\$3 with mask)).CLM.	US-PGPUB	OR	ON	2006/01/18 17:37
L3	1	((semiconductor with insulat\$4) or SOI) and (hard adj mask) and ((opening or trench or via or recess) with semiconductor) and (lateral\$3 with (etching or removing)) and implant\$5 and (anneal\$3 or heat\$3) and ((fill\$3 or deposit\$3) with (opening or trench or via or recess)) and (remov\$3 with mask)).CLM.	US-PGPUB	OR	ON	2006/01/18 17:38